Yasuhito Gotoh

List of Publications by Year
in descending order

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82	186	1478280 6	1199470 12
papers	citations	h-index	g-index

82	82	82	119
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Gamma-ray irradiation effects on CdTe solar cell dosimeter. Japanese Journal of Applied Physics, 2021, 60, SBBF02.	0.8	5
2	Development of a Field Emission Image Sensor Tolerant to Gamma-Ray Irradiation. IEEE Transactions on Electron Devices, 2020, 67, 1660-1665.	1.6	8
3	Expecting Further Development of Electron Beam Technologies. Vacuum and Surface Science, 2020, 63, 2-2.	0.0	0
4	Observation of DC fieldâ€evaporated ion species extracted from transition metal nitride thin film deposited on tungstenâ€tip. Surface and Interface Analysis, 2019, 51, 61-64.	0.8	1
5	Recent progress in development of radiation tolerant image sensor with field emitter array. , 2018, , .		1
6	Operation of field emitter arrays under high dose rate gamma-ray irradiation. , 2018, , .		1
7	Gamma-Ray Irradiation Effects of CdS/CdTe Photodiode for Radiation Tolerant FEA Image Sensor. , 2018, , .		1
8	Towards Establishing Our Forum for More Fruitful and Productive Scientific Discussions. Vacuum and Surface Science, 2018, 61, 328-333.	0.0	1
9	Robustness of field emitter arrays against high-energy X-ray irradiation at high dose rate. , 2017, , .		1
10	Process technology for volcano-structured double-gate Spindt-type field emitter arrays. , 2017, , .		0
11	Large magnification of electrostatic divergent lens system with extremely short focal length for ion and electron microscopy. , 2017, , .		0
12	System for Evaluation of Electron Emission Properties of Field Emitter Arrays under X-ray Irradiation. Journal of the Vacuum Society of Japan, 2017, 60, 328-333.	0.3	1
13	Novel Applications of Field Emitter Arrays ∼Towards Electron Devices under Harsh Environments and Light Sources∼. Journal of the Vacuum Society of Japan, 2017, 60, 55-63.	0.3	5
14	Gammaâ€ray tolerance of CdS/CdTe photodiodes for radiation tolerant compact image sensor with field emitter array. Physica Status Solidi C: Current Topics in Solid State Physics, 2016, 13, 635-638.	0.8	14
15	Radiation tolerance of compact image sensor with field emitter array and cadmium telluride-based photoconductor. , 2016, , .		5
16	Evaluation of current density distribution of field emitted electrons by numerical simulation in conjunction with analytical approach. , 2016, , .		2
17	Development of CdTe based photoconductive target for radiation tolerant compact image sensors. , 2016, , .		1
18	Evaluation of Ge Oxidation State in Ge Nanoparticles Formed in Thin SiO₂ Layer by Negative-Ion Implantation and Successive Two-Stage Annealing. Transactions of the Materials Research Society of Japan, 2016, 41, 305-308.	0.2	0

#	Article	IF	Citations
19	Potential Dangers and Safety Measures of Vacuum Technologies. Journal of the Vacuum Society of Japan, 2016, 59, 184-191.	0.3	2
20	Beam profile measurement of volcano-structured double-gated Spindt-type filed emitter arrays. , 2015, , .		0
21	Research project on development of radiation tolerant compact image sensor with a field emitter array. , 2015, , .		5
22	Emittance of compact microwave ion source for low energy application. Review of Scientific Instruments, 2014, 85, 02A721.	0.6	1
23	Evaluation of radiation tolerance of silicon dioxide layer for field emitter arrays. , 2014, , .		0
24	Operational characteristics of vacuum triode with hafnium nitride field emitter arrays in harsh environments. , 2014, , .		3
25	Titanium Dioxide Thin Film Deposition on Ag-Nanoparticles Embedded Silica Glass and Its Photocatalytic Properties. Transactions of the Materials Research Society of Japan, 2014, 39, 465-468.	0.2	0
26	Energy dependence of non-Rutherford proton elastic scattering spectrum for hafnium nitride thin film. Nuclear Instruments & Methods in Physics Research B, 2013, 315, 68-71.	0.6	3
27	Frequency mixing with a tetrode vacuum transistor. , 2012, , .		0
28	Production of extremely low energy electron beam with silicon-based field emitter arrays and its application to space charge neutralization of low-energy and high-current ion beam. , 2012, , .		0
29	Luminescence properties of Ge-implanted SiO<inf>2</inf> layer on Si substrate for blue-UV light source with low-voltage drive. , 2012, , .		0
30	Surface Modification of Silicone Rubber for Adhesion Patterning of Mesenchymal Stem Cells by Water Cluster Ion Beam. , 2011, , .		0
31	Collimator Magnet with Functionally Defined Profile for Ion Implantation. , 2011, , .		0
32	Ion Beam Neutralization Using FEAs and Mirror Magnetic Fields. , 2011, , .		2
33	Suppression of Divergence of Low Energy Ion Beams by Space Charge Neutralization with Low Energy Electrons Emitted from Field Emitter Arrays. AIP Conference Proceedings, 2011, , .	0.3	2
34	Osteoblast Patterning on Silicone Rubber by using Mesenchymal Stem Cells and Carbon Negative-Ion Implantation. Transactions of the Materials Research Society of Japan, 2011, 36, 317-320.	0.2	0
35	Degradation of Proteins for Neural Cell Adhesion Patterning by Carbon Negative-Ion Implantation. Transactions of the Materials Research Society of Japan, 2011, 36, 293-296.	0.2	0
36	Cell-Adhesion Patterning by using Carbon Negative-Ion Implantation into Albumin and Avidin Layers on Polystyrene. Transactions of the Materials Research Society of Japan, 2011, 36, 289-292.	0.2	0

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37	Piezoelectric Pb(Zr0.52Ti0.48)O3 thin films on single crystal diamond: Structural, electrical, dielectric, and field-effect-transistor properties. Journal of Applied Physics, 2010, 107, 024101.	1.1	11
38	P1–6: Compensation of divergence of space charge dominated ion beams using electron injection and confinement in non-uniform magnetic fields. , 2010, , .		1
39	11.1: Development of vacuum transistor using hafnium nitride field emitter array. , 2010, , .		1
40	10.4: Differences in deceleration performance of electrons emitted from field emitter arrays with different electrode geometries. , 2010, , .		1
41	Luminescence of SiO₂ Film Implanted with Ge Negative Ions. Transactions of the Materials Research Society of Japan, 2010, 35, 773-776.	0.2	1
42	Fine Adhesion Patterning and Aligned Nuclei Orientation of Mesenchymal Stem Cell on Narrow Line-Width of Silicone Rubber Implanted by Carbon Negative Ions. Journal of the Vacuum Society of Japan, 2010, 53, 191-193.	0.3	0
43	Development of in situ analyzer of field emission devices. , 2009, , .		0
44	Formation of low energy electron beam with silicon field emitter arrays for space charge compensation in low-energy ion-implantation system. , 2009, , .		0
45	Hafnium nitride field emitter array for field emission amplifier. , 2009, , .		1
46	Electron-emission properties of silicon field-emitter arrays in gaseous ambient for charge-compensation device. Journal of Vacuum Science & Technology B, 2008, 26, 782-787.	1.3	7
47	Thermal Diffusion Barrier for Ag Atoms Implanted in Silicon Dioxide Layer on Silicon Substrate and Monolayer Formation of Nanoparticles. AIP Conference Proceedings, 2006, , .	0.3	0
48	Germanium Nanoparticle Formation into Thin SiO2 Films by Negative Ion Implantation and Their Electric Characteristics. AIP Conference Proceedings, 2006, , .	0.3	0
49	Negative-ion implantation into thin SiO2 layer for defined nanoparticle formation. Review of Scientific Instruments, 2006, 77, 03A510.	0.6	6
50	Angular Distribution of Sputtered Ions from HfN by Ar+ Ion Bombarment. Hyomen Kagaku, 2005, 26, 449-453.	0.0	2
51	Discharge Characteristics of Micro Gas Jet Ion Source. Shinku/Journal of the Vacuum Society of Japan, 2004, 47, 285-288.	0.2	0
52	Fibrous structures on diamond and carbon surfaces formed by hydrogen plasma under direct-current bias and field electron-emission properties. Journal of Materials Research, 2003, 18, 305-326.	1.2	24
53	Formation and Control of Stoichiometric Hafnium Nitride Thin Films by Direct Sputtering of Hafnium Nitride Target. Japanese Journal of Applied Physics, 2003, 42, L778-L780.	0.8	22
54	Nanoparticle Formation in Surface Layer of Oxide Materials and Improvement of Photocatalytic Properties of Rutile Titanium Dioxide. AIP Conference Proceedings, 2003, , .	0.3	0

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55	In situ analyzer of electron emission properties: Fowlerâ€“Nordheim plotter and Seppenâ€“Katamuki plotter. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 1524.	1.6	3
56	Study on Optical Reflection Property from Multilayer on Si Substrate Including Nanoparticles in SiO2 Layer. Shinku/Journal of the Vacuum Society of Japan, 2003, 46, 698-702.	0.2	0
57	Development of in Situ Analyzer of Electron Emission Properties: Fowler-Nordheim Plotter and Seppen-Katamuki Plotter. Shinku/Journal of the Vacuum Society of Japan, 2003, 46, 550-553.	0.2	0
58	Development of Ion Beam Assisted Deposition System Equipped with a Low Energy Compact Microwave Ion Source. Shinku/Journal of the Vacuum Society of Japan, 2003, 46, 708-711.	0.2	0
59	Orientation Control of Niobium Nitride Thin Films by Ion Beam Assisted Deposition.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 215-218.	0.2	0
60	Nerve Cell Attachment Property of Absorbable Poly-Lactic-Acid Modified by Carbon Negative-Ion Implantation.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 514-518.	0.2	0
61	Magnetron Sputter Deposition of Transition Metal Carbide Thin Films and Their Evaluation as a Cold Cathode.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 212-214.	0.2	0
62	Control of Optical Absorption Band due to Cu/Ag Nanoparticles in SiO2 Glass by Dual Ion Implantation of Cu- and Ag-.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 528-532.	0.2	0
63	Improvement of Photocatalytic Efficiencies of Rutile TiO2 by Metal Negative Ion Implantation.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 177-180.	0.2	0
64	Evaluation of Hafnium and Tantalum Nitride Thin Films Prepared by Magnetron Sputter Deposition with a Nitride Target.. Shinku/Journal of the Vacuum Society of Japan, 2002, 45, 309-312.	0.2	0
65	A negative ion beam application for improving biocompatibility of polystyrene surface. AIP Conference Proceedings, 2001, , .	0.3	0
66	Observation of Negative-Ion-Implanted Polystyrene by Atomic Force Microscope for Improvement of Neural Attachment Properties.. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 217-220.	0.2	0
67	Negative-ion implanter for powders and its application to nanometer-sized metal particle formation in the surface of glass beads. Review of Scientific Instruments, 2000, 71, 804-806.	0.6	25
68	A negative ion beam application to artificial formation of neuron network in culture. Review of Scientific Instruments, 2000, 71, 797-799.	0.6	6
69	Extended Hueckel Molecular Orbital Calculation of Electron Density of Graphite Surface with Atomic Displacement.. Shinku/Journal of the Vacuum Society of Japan, 2000, 43, 607-610.	0.2	0
70	Fabrication of Gated Niobium Nitride Field Emitter Array.. Shinku/Journal of the Vacuum Society of Japan, 2000, 43, 251-254.	0.2	0
71	Properties of Niobium Nitride Thin Films As a Candidate for Cathode Material of Vacuum Microelectronics Devices.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 305-308.	0.2	0
72	Ion Energy Dependence of N/C Ratio in Low Energy CN Molecular Negative-ion Beam Deposited Films.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 229-232.	0.2	0

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73	Electron Emission Characteristics of Niobium Nitride Field Emitters Prepared by Ion Beam Assisted Deposition.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 309-312.	0.2	0
74	Evaluation of Uniformity and Depth Profiles in Negative-Ion Implantation into Spherical Powders.. Shinku/Journal of the Vacuum Society of Japan, 1999, 42, 345-348.	0.2	0
75	Extraction of molecular negative-ion beams of CN from radio frequency plasma-sputter-type heavy negative ion source for negative-ion beam deposition. Review of Scientific Instruments, 1998, 69, 884-886.	0.6	4
76	Surface charging of insulated materials by negative ion beam bombardment. , 1998, , .		0
77	Evaluation of Zirconium Nitride Thin Films Prepared by Ion Beam Assisted Deposition as a Candidate for Cathode Material of Vacuum Microelectronics Devices.. Shinku/Journal of the Vacuum Society of Japan, 1997, 40, 276-279.	0.2	2
78	CN Molecular Negative-Ion Extraction Properties from RF Plasma-Sputter-Type Heavy Negative-Ion Source and CN Negative-Ion Beam Deposition.. Shinku/Journal of the Vacuum Society of Japan, 1997, 40, 284-287.	0.2	0
79	Noise Power Analysis of the Stability of Micro-Field Emitters.. Shinku/Journal of the Vacuum Society of Japan, 1997, 40, 159-162.	0.2	0
80	Cone-shaped metalâ€“insulatorâ€“semiconductor cathode for vacuum microelectronics. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1996, 14, 1970.	1.6	4
81	Charging Simulation of Micro-structured Pattern in Ion Implantation.. Shinku/Journal of the Vacuum Society of Japan, 1995, 38, 228-230.	0.2	0
82	Charge-up Free Ion Implantation in Insulated Substrate using Negative Ion.. Shinku/Journal of the Vacuum Society of Japan, 1993, 36, 889-892.	0.2	0